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APPLICATION NO.	FIL	ING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/616,603	07/10/2003		Christophe Pierrat	FTIS 1001-1	3620	
22470	7590	10/07/2005		EXAMINER		
HAYNES 1	BEFFEL &	& WOLFELD L	CHACKO DAVIS, DABORAH			
P O BOX 366 HALF MOON BAY, CA 94019				ART UNIT	PAPER NUMBER	
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DATE MAILED: 10/07/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)					
Office Action Summer	10/616,603	PIERRAT ET AL.					
Office Action Summary	Examiner	Art Unit					
	Daborah Chacko-Davis	1756					
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the o	correspondence address					
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be ting will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	N. mely filed the mailing date of this communication. ED (35 U.S.C. § 133).					
Status							
1) Responsive to communication(s) filed on 03 A	<u>ugust 2005</u> .						
2a) ☐ This action is FINAL . 2b) ☑ This	This action is FINAL . 2b)⊠ This action is non-final.						
* *							
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 4	53 O.G. 213.					
Disposition of Claims							
4) Claim(s) 1-27 is/are pending in the application.	☑ Claim(s) <u>1-27</u> is/are pending in the application.						
	4a) Of the above claim(s) <u>1-15</u> is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.							
6) Claim(s) <u>16-27</u> is/are rejected.							
7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or	r election requirement						
are subject to restriction and/or	r election requirement.						
Application Papers							
9) The specification is objected to by the Examine							
•))☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.						
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
	ammer. Note the attached Office	; Action of form F 10-132.					
Priority under 35 U.S.C. § 119							
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of:							
_	 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 						
<u> </u>	3. Copies of the certified copies of the priority documents have been received in this National Stage						
	application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list of the certified copies not received.							
Attachment(s)							
1) Notice of References Cited (PTO-892)	4) Interview Summary						
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)	Paper No(s)/Mail D 5) Notice of Informal F	ate Patent Application (PTO-152)					
Paper No(s)/Mail Date <u>08/03</u> . 6) ☐ Other:							



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DETAILED ACTION

Election/Restrictions

1. Applicant's election without traverse of Group II, claims 16-27, in the reply filed on September 12, 2005, is acknowledged. Claims 1-15, are withdrawn from further consideration pursuant to 37 CFR 1.142(b) as being drawn to a nonelected invention, there being no allowable generic or linking claim.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 3. Claims 16-20, are rejected under 35 U.S.C. 102(b) as being anticipated by U. S. Patent No. 5,121,256 (Corle et al).

Corle, in col 1, lines 56-60, in col 2, lines 1-68, in col 3, lines 31-36, and lines 42-54, in col 4, lines 1-14, discloses a process for making integrated circuits comprising positioning a photoresist layer coated sample on a substrate holder (see figure 5), in a lithography system, providing a photomask (layout object) to be imaged on the sample, placing the photoresist coated sample very close to the projection lens (objective lens with an SIL), and imaging the photoresist (to form patterns) by projecting the laser from the illuminating source through the mask and the lens, such that standing waves form between the bottom surface of the lens and the top surface of the photoresist layer

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(claims 16-18). Corle, in col 3, lines, 48-68, discloses positioning the lens in very close proximity to the photoresist sample (not adhering to the sample), and prevents contact vibrations from each other (claim 19). Corle, in col 2, lines 1-45, discloses that the lens (projection lens) and the mask are placed in close contact (see figure 5) and that the lens system includes a lens element of high refractive index (claim 20).

Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 21-27, are rejected under 35 U.S.C. 103(a) as being unpatentable over U.
- S. Patent No. 5,121,256 (Corle et al).

Corle, is discussed in paragraph no. 3.

The difference between the claims and Corle is that Corle does not disclose the claimed proximity correction using a lithography model as recited in claims 21-27.

Corle, in col 2, lines 63-68, in col 3, lines 1-4, discloses implementing techniques for proximity corrections.

Therefore, it would be obvious to a skilled artisan to implement proximity correction based on lithography models because it is known in the art of lithography systems to use such methods of proximity correction for the purpose of providing improved definition in the transfer of patterns.

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Conclusion

6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daborah Chacko-Davis whose telephone number is (571) 272-1380. The examiner can normally be reached on M-F 9:30 - 6:00. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (571) 273-8300. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

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September 30, 2005

JOHN Ä. MCPHERSON PRIMARY EXAMINER